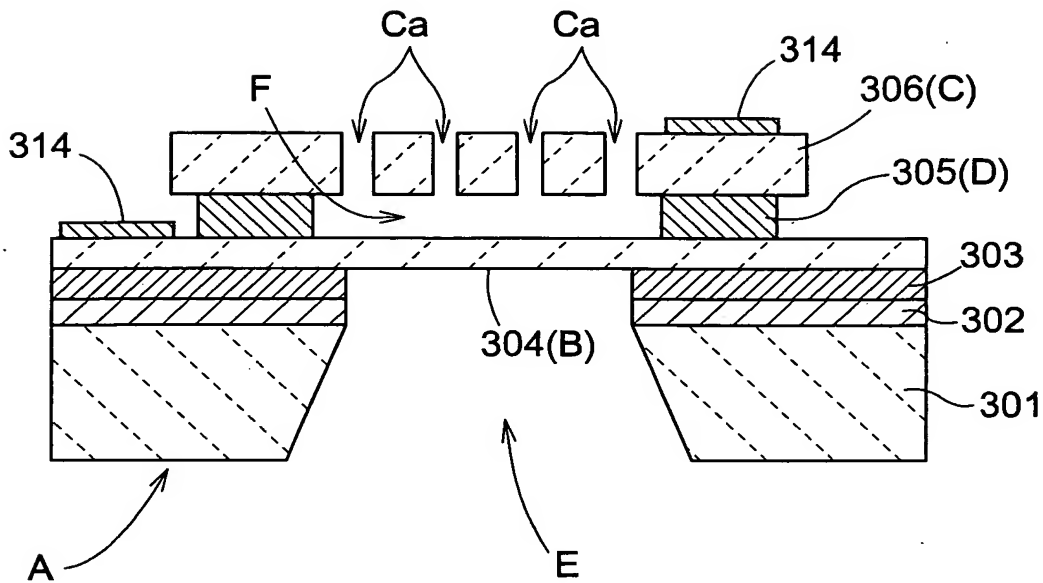


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FIG.1

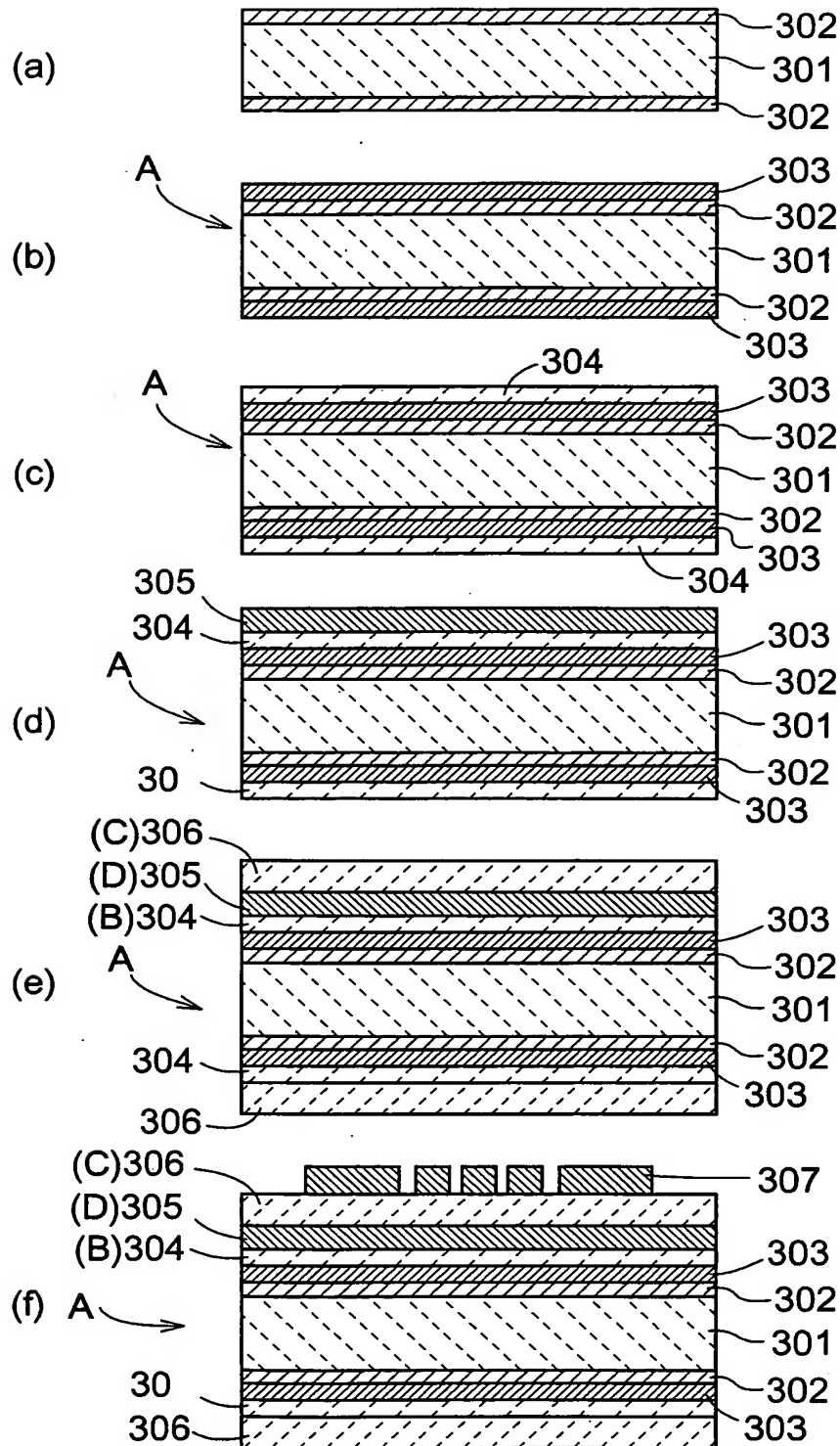


A: support substrate  
 B: diaphragm  
 C: back electrode  
 D: spacer  
 E: acoustic opening  
 F: void area

301: monocrystal silicon substrate  
 302: silicon oxide film  
 303: silicon nitride film  
 304: membrane, or polycrystal silicon film  
 305: sacrificial layer  
 306: polycrystal silicon film  
 314: take-out electrode

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FIG.2



(g)

(h)

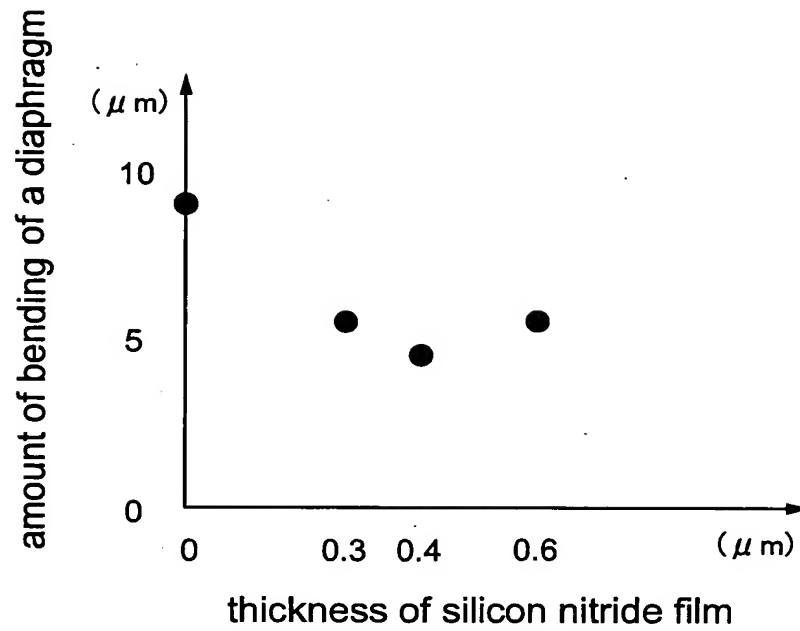
(i)

(j)

(k)

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FIG.4



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FIG.5

